

Filed

February 3, 2004

**REMARKS**

In response to the Office Action mailed June 12, 2003, Applicant respectfully requests the Examiner to reconsider the above-captioned application in view of the above amendments and the following comments.

**Discussion of Substitute Specification**

Applicant has amended the specification to be written in full, clear, and exact terms to meet the requirement of 35 U.S.C. § 112, first paragraph.

Additional description referring to Figures 1-7 has been provided within the original disclosure of the application. The specification has been amended to reflect the drawing amendments. Also, the specification has been amended to place a portion of the Background of the Invention section, which is related to the invention, in the Detailed Description section. In addition, the specification has been amended to include a description of the well known terms "epitaxially grown" and "diamond-like material" which is consistent with the original disclosure. Thus, the amendments to the specification are supported by the original disclosure.

According to 37 C.F.R. § 1.125, Applicant hereby submits a substitute specification. All the changes (including the matter being added to and the matter being deleted from) made in the substitute specification are supported by the original specification and drawings. Thus, the substitute specification includes no new matter. A marked up version of the substitute specification showing all the changes to the specification, and a version of the substitute specification without markings as to amended material are submitted with this paper. On the marked up version, the additions are underlined while the ~~deletions are struck through~~.

**Discussion of Objections of the Drawings**

The Examiner has objected to the drawings as failing to comply with 37 CFR § 1.84(p)(5). The Examiner notes that reference character "01" has been used to designate different parts in different embodiments in Figures 3a, and 4a-4e. The Examiner also notes that reference characters "01," "03," "04," and "06" have been used to designate different parts in different embodiments. In reply, as discussed above, Figures 3b, 4a-4e, 5a-5d, 6a, 6b, and 7 have been amended to comply with 37 CFR § 1.84(p)(5). In view of the above, withdrawal of the drawing objections is respectfully requested.

**Discussion of Objections of the Specification**

The Examiner has objected to the disclosure because of the following informalities: it fails to adequately describe the claimed invention in such a manner as to enable any person skilled in the art to make and use the claimed invention without involving extensive and undue experimentation.

In the June 19, 2003, telephone conference with the undersigned, the Examiner confirmed that if the specification is amended to include additional description referring to the drawings, and description regarding "epitaxially grown," this specification objection would be removed. As discussed above and reflected in the substitute specification, the substitute specification includes additional description regarding Figures 1-7 and the description for the term "epitaxially grown." In view of the above, withdrawal of the objection is respectfully requested.

The Examiner also asserts that the complete disclosure should be revised to comply with the format required by 37 CFR §1.77. Applicant submitted a substitute specification in the previous response. The substitute specification includes 1) title of the invention, 2) background of the invention, 3) summary of the invention, 4) brief description of the drawings, 5) detailed description of the invention, and 6) abstract. A complete set of amended claims have also been provided in the previous response. In view of the above, Applicant respectfully submits that the specification complies with 37 CFR §1.77. Withdrawal of the objection is respectfully requested.

**Discussion of Claim Rejections Under 35 U.S.C. 112, § 1**

The Examiner has rejected Claims 82-88 under 35 U.S.C. 112, first paragraph, as containing subject matter which was not described in the specification. The Examiner asserts that the specification fails to disclose how the different steps of forming the claimed invention are actually reduced to practice.

In the June 19, 2003 telephone conference with the undersigned, the Examiner confirmed that if the specification is amended to include additional description referring to the drawings and some description regarding "epitaxially grown," this claim rejection would be removed. As discussed above and reflected in the substitute specification, the substitute specification includes additional description regarding Figures 1-7 and the description for the term "epitaxially grown." In view of the above, withdrawal of the rejections is respectfully requested.

**Discussion of Claim Rejections Under 35 U.S.C. 112, ¶ 1**

The Examiner has rejected Claims 59-60, 77 and 81 under 35 U.S.C. 112, second paragraph as being indefinite. The Examiner asserts that Claims 59-60, 77 and 81 are indefinite as it is not clear what the applicant intended to cover with the use of the phrase "diamond-like material." Applicant respectfully submits that the term "diamond-like material" is definable and widely used. As an example, the 14<sup>th</sup> European Conference on "Diamond-like material" has been held on September 7 through 12, 2003. A copy showing the title of the conference is enclosed herewith.

In addition, as discussed in the substitute specification, diamond-like material consists of carbon atoms having a non-diamond structure, i.e., this relates to a crystal type. The diamond like materials differ from a diamond in "sp<sup>2</sup>" and "sp<sup>3</sup>" orbital portions of chemical bondings. This term has been commonly used worldwide for at least the past 10-20 years.

The Examiner asserts that Claim 67 is indefinite as it is not clear how the different elements of the claimed invention are related to one another. However, Applicant respectfully submits that all of the elements "substrate," "field emitter," "source" and "ballast resistor" of Claim 67 are interconnected to one another as clearly recited in the claim. In view of the above discussion, Claims 59-60, 67, 77 and 81 are clear and definite. Withdrawal of the rejections is respectfully requested.

**Discussion of Rejection of Claims Under 35 U.S.C. § 102(b)**

The Examiner has rejected Claims 51-53, 55, 56, 58, 61-66 under 35 U.S.C. § 102(b) as being anticipated by Borel, et al. (U.S. Patent No. 4,940,916). However, all of the above claims are patentably distinguished from the prior art as discussed below.

**Rationale of 35 U.S.C. § 102**

"For a prior art reference to anticipate a claim in terms of 35 U.S.C. § 102, every element of the claimed invention must be identically shown in a single reference." *Diversitech Corp. v. Century Steps, Inc.*, 850 F.2d 675, 677, 7 USPQ 2d 1315, 1317 (Fed. Cir. 1988). Applicant respectfully submits that Claims 51-53, 55, 56, 58, 61-66 are not anticipated by the Borel reference as discussed below because the prior art reference lacks at least one of the above limitations recited in each of the rejected claims.

### Discussion of Patentability of Independent Claim 51

Claim 51 recites, among other things, a field emitter, a body of the field emitter being a whisker epitaxially grown on the substrate. The semiconductor terminology "epitaxially grown on the substrate" means grown with the same crystal structure as the substrate. Also, "a body of the field emitter being a whisker epitaxially grown" means that the length of the field emitter body is significantly greater than the width of the field emitter body, as shown in the specification as " $l/d > 1$ ."

The Borel reference does not disclose a structure that is "epitaxially grown on the substrate." Referring to Figure 4, the Borel patent only discloses that the micropoint (field emitter: 12) is deposited on the second resistive layer (24) of the conductive layer (5). That is, Borel does not disclose "a field emitter, a body of the field emitter being a whisker epitaxially grown on the substrate" recited in Claim 51. In view of the above, Claim 51 is not anticipated by the Borel reference, and thus the claim is patentable.

Furthermore, in the June 19, 2003 telephone conference with the undersigned, the Examiner confirmed that if the specification is amended to include a description of "epitaxially grown," this claim rejection would be removed. As discussed above, the specification has been amended to include the description regarding "epitaxially grown." Thus, withdrawal of the rejections is respectfully requested.

### Discussion of Patentability of Dependent Claims

Claims 52-53, 55, 56, 58, and 61-66 depend from base Claim 51 and further define additional technical features. In view of patentability of their base claim and further additional features, the dependent claims are also patentable. Thus, withdrawal of the rejections is respectfully requested.

### Discussion of Rejection of Claims Under 35 U.S.C. § 103(a)

The Examiner has rejected Claims 54, 59, and 60 under 35 U.S.C. § 103(a) as being unpatentable over Borel, et al. (U.S. Patent No. 4,940,915). Claims 54, 59 and 60 depend from independent Claim 51 and further define additional technical features. As discussed above, Claim 51 is patentable over the Borel reference. In view of patentability of their base claim and

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further additional features, Claims 54, 59 and 60 are also patentable. Thus, withdrawal of the rejections is respectfully requested.

### CONCLUSION

In view of the foregoing amendments and remarks, it is respectfully submitted that the present application is in condition for allowance. If the Examiner has any remaining concerns which might prevent the prompt allowance of the application, the Examiner is respectfully invited to contact the undersigned at the indicated telephone number.

Respectfully submitted,

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PATENT

ELECTRONS SOURCES WITH WHISKER FIELD EMITTERS,  
AND METHOD OF MANUFACTURING

BACKGROUND OF THE INVENTION

FIELD OF THE INVENTION

[0001] This invention relates to microelectronics, including vacuum microelectronics, in particular to field emission devices, specifically to field emission cathodes, as well as to other field emission devices such as field emission displays, electron sources for electron guns, for microwave devices, etc.

DESCRIPTION OF THE RELATED TECHNOLOGY

[0002] During the last few years, various versions for realization of field emission, including the emission with using of defects in planar structures, have been considered, the defects acting as initiators of the field emission [1,2]. Field emitters such as tips and blades prepared by special methods, as field emission initiators, have many advantages in comparison with the defects from the point of view of feasibility to realize regular multiple arrays of the field emitters and controlled growing of the arrays on large areas. However, cases often occur at the practice when the regular arrays are inferior to structures with an incidental distribution of the defects in homogeneity.

[0003] Troubles in stability and controllability of electron flows given off by the field emitters are also known. Troubles with uniformity of the field electron emission of the multiple field emitter arrays are of the same nature. The uniformity is typically ensured by ballast resistors that equalize electron currents through different field emitters of the multiple field emitter arrays.

[0004] Various design and technological solutions are used for overcoming of the troubles (problems) with the field emitter.

[0005] A controlled electron source is known where the field emitter is connected to the drain of MOSFET that serves as a stable current electron source [3,4]. In such an electron

source, the issue of stability and controllability of the field emission current is successfully solved. However, transistor p-n junctions in the electron source are placed in the substrate where the field emitter is placed, too, and a substrate, too. This increases significantly the area taken by a pixel and, accordingly, decreases the resolving power of field emission displays based on such electron sources.

[0006] A solution of the problems of stability and controllability combined with the spatial arrangement of the control components is successfully realized in the patent [5]. Figure 1 illustrates the field emission cathode according to the prior art [5]. In Figure 1, reference numerals 1-4 represent a substrate, a cathode, a diode, and a metallic layer, respectively. Also, reference numerals 5-8 represent a semiconductor layer, an emitter, an insulating layer, and a control electrode, respectively. Here, in the electron source the diode (3) is placed in the emitter base for the stability and the controllability of the field emission current. Such a design decreases principally the sizes of the electron source three times, as minimum, because its control component takes the same place as the field emitter itself. Such an electron source allows to regulate the voltage so that the starting voltage for the field emission is decreased and, in such a way, the uniform emission is ensured. A plurality of emitters, acting through diodes and operating actually as ballast resistors, are placed onto the cathode electrode. Such a design ensures the uniformity of the field emission and, simultaneously, its controllability. However, the proposed in [5] components of stabilization and control of the field emission current are insufficient for successful solving of the problems of uniformity and controllability.

[0007] In the patent [6] a more complete using of the advantages of the field emitters is realized. The field emitter is considered as a spatially distributed object (various parts of which serve as functional components of a device) rather than as a "material point" of the field emission, without spatial characteristics of their various parts.

[0008] According to the patent [6] components for control of the electron source are transformed from the planar arrangements, as it was done in [3,4], into a vertical arrangement. Figure 2a and 2b illustrate the field emission devices according to the prior art [3]. Thus, a principal role in the stabilization and control of the field emission current is assigned (allocated), to the body and to the surface of the field emitter, in addition to the usual role of its top.

[0009] Figures 3a and 3b illustrate the field emission devices according to the prior art [6]. In Figures 3a and 3b, reference numeral 01 represents a top of field emitter. Reference

numeral 02 represents a control electrode. Reference numerals 03 and 03a represent an insulator. Reference numerals 04 and 06 represent a barrier (junction). Reference numeral 08 represents a control electrode. Reference numerals 09 and 09i represent a conductive part of substrate and an insulator part of substrate, respectively.

[0010] Figure 3c illustrates the field emitter with various function areas of the prior art. In Figure 3c, reference character E represents an external electric field. Reference character  $E_j$  represents various positions of a junction boundary (for example, p-n junction) under the influence of external electric fields of various values. Reference character  $E_a$  represents the position of the junction boundary when electrons start to flow through the junction. Reference characters l and d represent the length of the active area and width of the active area, respectively.

[0011] Figure 3d illustrates the method for preparation of the field emitter according to [6]. Reference numerals 12, 13, and 14 represent layers with different kinds of conductivity. In Figures 3a-3d, reference characters a, b and c (i.e., not associated with any reference numeral) represent areas of various kinds of conductivity. Reference character e represent position of active areas. Similar to [3-5] in the patent [6] an extracting electrode acts to electrons placed in the emitter top. In [6] electron sources are considered where the field emitters have sufficient length and thickness. Therefore, from the point of the action of the control electrodes or barriers (such as the diode in [5]), as minimum four areas of the electron sources are considered: -the substrate on which the field emitter is placed; -the basis of the field emitters; -the top of the field emitters; -their bodies. These are areas of selective activation, or active areas. So, the active area is an area in the substrate, in body of the field emitter, in its basis or at its top. A connection of the source of the charge carriers with the field emitter is implemented through the areas, and a control of the field emission current (of the charge carriers flow) from one area to another by means of stimulation and extracting is implemented.

[0012] In some cases, however, such a control of the charge carrier flow can not be realized in [6]. This is related to the fact that the field emitter, being under the action of a rather high electric field, for example, of the anode one, is subjected to its influence not only to the area of the top of field emitter but also all over the body. As a result, such an electric field, acting to the field emitter, "shorts out" an action various barriers and over control components. The method for preparation of the field emitters by "wet" or "dry" etching used in the patent [6]



results in formation of the emitters having small ratios of the length  $l$  of the active area to its diameter  $d$ . In this case, for controlling of the field emission current, a very large voltage must be used in order to compensate the action of the large external (for example, of anode) electric field.

[0013] Indeed, if the field emitter, containing a part with the p-type conductivity is placed in the electric field  $E$  (Fig. 3c), formed by the anode, the boundary of the first of the first p-n junction 04 is shifted  $E_j$  to the p-area. At a certain value  $E_0$ , the first junction 04 approaches to the second one 06 in such an extent that the electrons from the n-area  $c$  begin tunneling through the narrowed barrier to the field emitter. This causes emission of electrons from field emitter. This is the "shorting out" under the external electric field. Existence of the control electrode near the field emitter both in traditional (Fig. 3a) and in the considered [6] version (Fig. 3b) can compensate the action of the penetrating electric field and, such a manner, to "lock" the charge carriers of the second n-area  $c$ . However, it is known that, at the geometric sizes, considered in [6], the length  $l$  of the p-area is compatible with or and even shorter than the width  $d$ . As it is known, for "locking" of the charge carriers value of the traverse electric field of the control electrode 02 or 08 must be comparable with the longitudinal field responsible for the charge carrier flow. This makes it necessary to apply large voltages to the control electrodes.

[0014] In addition, in the patent [6] the control electrodes stimulate the flowing of the charge carriers through the active area and extract the electrons from the field emitter. In such a way, the electron emission is stabilized and controlled. At the same time the control electrodes in [6] does not lock the flow of the charge carriers through the active area. The above function of the control electrodes-to stimulate the flowing of the charge carriers, makes it necessary mentioned in [6] approximate sizes of p-area as "... formed to no more than several microns in thickness and generally to submicron order thickness" (see column 8, last paragraph in [6]). This means that the authors of [6] did not consider a possibility to provide the control electrode by "locking" function and, as a result, they considered the design which is enough just for stimulation and which is not enough for locking the electrons moves under the influence of strong external electric field. However, it is known that if the control electrodes can lock the flow, it is possible to use small (in absolute value) negative voltage for the locking of the flow. This approach is very important from practical point of view-to use low voltage "electric keys" in different driving systems, for example, in the field emission displays. Such a version can not be

realized in [6] due to small value of the characteristic  $l/d$  that is the approximately equal to 1 which is provided by the design proposed in [6].

### SUMMARY OF THE INVENTION

[0015] An electron source is proposed, the source including a field emitter, a substrate, a source of charge carriers, and at least one ballast resistor. The field emitter is implemented of a whisker epitaxially grown on the substrate, and at least one ballast resistor is implemented as a barrier which is represented as a boundary in the body of the field emitter. The boundary is formed by a contact of materials with different kinds of conductivity.

[0016] In the electron source the field emitter is implemented of at least one semiconductor material. At least one barrier in the electron source is formed by junction of materials with different kinds of conductivity, such as n, n+, p, p+ kinds. At least one barrier is formed by an insulating layer that is across to direction of charge carriers flow.

[0017] The field emitter is formed by a tip, the tip consisting of two coaxial parts, a broad lower part and a narrower upper part. The field emitter can be also formed by a blade. The tops of the field emitter are sharpened and coated by diamond or diamond-like material, and the coatings can be sharpened too.

[0018] At another version of the electron source the barrier is formed by a boundary between a body of the field emitter and a conducting layer placed on a surface of the field emitter. In the electron source, at least one ballast resistor is implemented as a barrier which is represented as a boundary in the field emitter body, the boundary being formed by contacts of the materials with different kinds of conductivity.

[0019] The field emitter is implemented of at least one semiconductor material, and the conducting layer is also implemented of at least one semiconductor material.

[0020] At least one barrier in the field emitter is formed by junction of materials with different kinds of conductivity, such as n, n+, p, p+ kinds.

[0021] In another version of the electron source at least one barrier is formed by an insulating layer that is across to the direction of charge carriers flow.

[0022] The field emitter can be formed either by a tip or by a blade. In the case of the tip shape the field emitter consists of two coaxial parts, a broad lower part and a narrower upper part. The top of the field emitter is sharpened and coated by diamond or diamond-like material,

the coating being sharpened. The diamond-like material consists of carbon atoms having a non-diamond structure, i.e., this relates to a crystal type. The diamond-like materials differ from a diamond in  $sp^2$  and  $sp^3$  orbital portions of chemical bondings. This term has been used worldwide for at least the past 10-20 years.

[0023] The source of the charge carriers is connected to the field emitter via substrate and/or a conducting layer placed on a surface of the field emitter directly or via an insulating layer.

[0024] In one more version of the electron source the substrate has a shape of a tip and is formed by an insulator and by a conductive layer, the ballast resistor being implemented by the layer.

[0025] The conductive layer in the electron source contains at least one barrier for charge carriers. At least one barrier in the electron source is formed by junction of materials with different kinds of conductivity, such as n, n+, p, p+ kinds, and at least one barrier is formed by insulating layer that is across to direction of charge carriers flow.

[0026] In one more version the electron source can be controlled containing at least one control electrode. The electron source can contain at least one active area in the body and/or on the surface of the field emitter. The active area can be realized in conducting layer placed on the surface of the substrate and/or of the field emitter directly or via an insulator layer.

[0027] At least one control electrode is placed close to one barrier for the charge carriers or on side surface of the field emitter via an insulator layer. The control electrode is separated from the field emitter by a vacuum gap or placed along the field emitter. The control electrode can have a direct contact with the side surface of the field emitter.

[0028] The substrate in the controlled electron source can be crystalline, or can be implemented by an insulator and a conductive layer placed on the insulator. The substrate can be implemented of the single-crystalline material with orientation (111).

[0029] The surface of the substrate can be coated by a material which is transparent for electrons and which prevents outlet of chemical elements from the surface of the controlled electron source, the material being diamond or diamond-like carbon.

[0030] The invention also considers a matrix of the controlled electron sources containing at least two controlled electron sources. The matrix can contain a two-dimensional system of mutually perpendicular rows of the controlled electron sources, at least one of the

control electrode of the electron sources having a diaphragm shape and being implemented of diamond or diamond-like material.

[0031] The substrate on which the controlled electron source is arranged is implemented of conductive material placed on an insulator.

[0032] The matrix contains conductive buses which form two systems where buses of each of the systems are mutually parallel whereas the buses of two different systems are mutually perpendicular, the two systems being placed in two levels and separated by an insulating layer.

[0033] This invention proposes also a method for preparation of controlled electron sources including a formation on a solid substrate of field emitters each of that contains at least one transverse junction formed by materials having different electrical conductivity, a formation of at least one controlled electrode close to such junctions, where the field emitters are implemented of whiskers epitaxially grown by the vapor-liquid-solid mechanism. The implementation of the field emitters can include formation of the hollows in the substrate and deposition of solvent particles at the bottom of the hollows. The implementation of the field emitters can also include placing of solvent particles on the substrate and etching of the substrate around the particles.

[0034] As mentioned above, the method can include further procedure for formation of the field emitters, that is to say, placing of a source material, having a first kind of conductivity, opposite to the substrate with the solvent particles on it, growing of whiskers having the first kind of conductivity, stabilized cooling of the grown whiskers, having the globules on its tops, with an introduction of an inert gas into atmosphere, with simultaneous decreasing of the temperature of the substrate, changing of the source material for another source having a second kind of conductivity, stabilized heating of the grown whiskers, having the globules on its tops, with an introduction of an inert gas into atmosphere, with simultaneous increasing of the temperature of the substrate, and growing of whiskers having the second kind of conductivity. The method also includes possibility to change the source materials more than two times.

[0035] As mentioned above, the method can also include further procedure for formation of the field emitters includes growing of whiskers in a gaseous atmosphere containing the element or elements of which the substrate consists, introduction of doping gaseous

compounds into the gas atmosphere. According to the method the formation of the field emitters can include more than one procedure of introduction into the gas atmosphere of different gaseous doping compounds.

#### BRIEF DESCRIPTION OF DRAWINGS

- [0036] Fig. 1 illustrates the field emission cathode according to the prior art [5].
- [0037] Figs. 2a, 2b illustrate the field emission devices according to the prior art [3].
- [0038] Figs. 3a, 3b illustrate the field emission devices according to the prior art [6].
- [0039] Fig. 3c illustrates the field emitter with various function areas of the prior art.
- [0040] Fig. 3d illustrates the method for preparation of the field emitter according to [6].
- [0041] Figs. 4a, 4b, 4c, 4d, 4e illustrate the stabilized electron sources according to the present invention.
- [0042] Figs. 5a, 5b, 5c, 5d illustrate the controlled electron sources according to the present invention.
- [0043] Figs. 6a and 6b illustrate the matrix system of the controlled electron sources according to the present invention.
- [0044] Fig. 7 illustrates grown silicon whisker with transversal barriers (junctions).

#### DETAILED DESCRIPTION OF THE INVENTION.

[0045] In this invention, the drawback is overcome owing to the fact that. Here, for stabilization and controlling of the field emission, a whisker ("filament crystal") characterized by  $l/d \gg 1$  is used. Here as discussed above, reference characters  $l$  and  $d$  represent length of the active area and width of the active area, respectively. A method for preparation of the whiskers with traverse p-n junctions is also proposed in this invention. As a result, the design proposed allows to control the field emission by locking the charge carrier flow.

[0046] The approach proposed is especially important at creation of effective long-living flat panel displays. Indeed, the higher the anode (accelerating) electric field, the more effective and long-living are their phosphors because, the efficiency is larger at higher voltages. Also at the increasing of anode voltage in such devices and, accordingly, decreasing of the current the durability of the phosphors is increased. The high accelerating voltage allows to use

a protecting coating layer (for example, aluminum) that prevents the decomposition of the phosphors and increases the illumination owing to the light reflection. In addition, the decreasing currents are useful for the field emitters themselves (especially of semiconductor emitters) because at high currents the emitters are heated resulting in their degradation.

[0047] In this invention various possibilities for the stabilization and control of the field emission current based on using of epitaxially grown whiskers are proposed. By whisker growing, the ratio  $l/d$  can be implemented as 5-10 and more times. In addition, with the whisker grown field emitters broad possibility for shape variation and creation of the control electrodes can be realized. In particular, a design with step-shaped emitter is proposed in Fig. 4c.

[0048] According to this invention, the field emitter is implemented of whisker that includes at least one barrier (for example, n, n+, p, p+ or p-n junction), i.e., the barrier is placed in the body of the field emitter, being at some height  $h > 0$  (Fig. 4a) above the substrate, i.e., above its own basis. At the same time in the patents [3,5] one of the barrier is placed at the basis of the field emitter being either at the upper level of the substrate or below it.

[0049] As it was mentioned above the active area can be placed both in the basis of field emitter [5], top [3,5] or substrate [3], and in the body of the field emitter [6]. In this invention a version is proposed when the active area is placed on side surface of the field emitter or in the body of the material that has direct or indirect contact with substrate or field emitter.

[0050] The active area can be placed also in thin surface conductive layer arranged on an insulating substrate. Thus, the version of the controlling electron source as purposed in this invention not only has solved the problem of transferring the stabilizing and controlling components from their planar arrangement to vertical one (and, in such a way, of increasing the resolution of the device) but also allows to conserve the controllability of the emission current by means of low voltage. In such a way, this allows to realize said controllability both in the case of low and high external electric field.

[0051] In the patent [6], as it was mentioned above, the method for fabrication of the field emitters with traverse p-n junctions. However, this method does not allow to obtain optimal geometric parameters of the field emitter that gives necessary functional characteristics.

[0052] The methods for growing oriented whiskers arrays are known [7,8,9,10]. The methods, however, do not contain procedures for preparation of the junction, for example, like p-n junctions. In this invention, such procedures are proposed.

[0053] Figures 4a-4e illustrate the stabilized electron sources according to the present invention. In Figures 4a-4e, reference numerals 01a, 01b, and 01c represent a top of the field emitter. Reference numeral 03b represents an insulator if charge carriers are provided via the surface layer. Also, the insulator (03) can be a conductive material if charge carriers are provided via the substrate.

[0054] Reference numerals 04a-04e, and 06a-06c represent a barrier (for example, p-n junction). Reference numeral 09 represents a conductive part of the substrate. Reference numeral 09i represents an insulator part of the substrate. In Figures 4a-4e, reference characters a, b, c (i.e., not associated with any reference numeral) represent areas of various types of conductivity. Reference character q represents the possible movement of charge carriers. Reference character h represents the height of the position of the barrier above the substrate.

[0055] Throughout the specification, the term "epitaxially grown" means 1) the tip has the same crystalline structure as the substrate, and 2) the tip has a "extended" form, so the relation of the length to its diameter significantly greater than 1 as reflected in the formula  $l/d \gg 1$  and shown in Figures 4-6.

[0056] EXAMPLE 1. A most typical version for realization of the stabilized electron sources that uses a barrier as a ballast resistor is the following. A thin layer of n-type silicon is deposited onto p-type silicon tip that epitaxial to substrate (Fig. 4d). The junction between the p-type of silicon and then-type silicon coating acts as a ballast resistor. Figures 5a-5d illustrate the controlled electron sources according to the present invention. In Figures 5a-5d, reference numeral 01d represents a top of the field emitter. Reference numerals 03c and 03d represent an insulator if charge carriers are provided via the surface layer. The insulators (03c and 03d) can be a conductive material if charge carriers are provided via the substrate.

[0057] Reference numerals 04f, 04g, 06c represent a barrier (for example, p-n junction). Reference numeral 08 represents a control electrode. Reference numeral 09 represents a conductive part of the substrate. In Figures 5a-5d, reference characters a, b, c (i.e., not associated with any reference numeral) represent areas of various types of conductivity. Reference character e represents position of active areas.

[0058] EXAMPLE 2. A most typical version for realization of the controlled electron sources that uses a vertical arrangement of the control components is the following. The tip contains in its body two p-n junctions. An upper part of the tip is implemented of n-type

material. A lower part of tip as well as the adjacent substrate is implemented of n-type material. A control electrode is placed at a middle part of the tip which is implemented of p-type material. The control electrode has an extended length, is placed on the surface of the tip and has with it a direct contact (Fig. 5c). When a voltage VOPD is applied to the control electrode, an inverse layer is induced at the area b along the surface of the field emitter, and electrons from the area c begin to penetrate into area a through the inverse layer. Then the electrons are emitting from the field emitters under the action of the anode voltage. Figures 6a and 6b illustrate the matrix system of the controlled electron sources according to the present invention. In Figures 6a and 6b, reference numeral 01 represents a top of the field emitter. Reference numerals 02a and 02b represent a control electrode. Reference numeral 03c represents an insulator if charge carriers are provided via the surface layer. The insulator (03c) can be conductive material if charge carriers are provided via the substrate. Reference numeral 03' represents an insulating glass layer.

[0059] Reference numerals 04h, 06d, 06e represent a barrier (for example, p-n junction). Reference numeral 07 represents a centrosymmetrical cavity. Reference numeral 08 represents a control electrode. Reference numeral 09 represents a conductive part of the substrate. Reference numeral 09i represents an insulator part of the substrate. In Figures 6a and 6b, reference characters a, b, c (i.e., not associated with any reference numeral) represent areas of various types of conductivity. Reference numeral 09' represents a conducting substrate of silicon having the crystallographic orientation (111).

[0060] In Figure 6a, rows of control electrodes 02a, 02b, and 08 are mutually perpendicular, and together perform the controlling of the emission of the matrix system. In Figure 6b, rows of control electrodes 02a, 02b, and rows of the conductive part 09 of substrate based on the insulator part 09i of the substrate are mutually perpendicular, and together perform the controlling of the emission of the matrix system.

[0061] Figure 7 illustrates grown silicon whisker with transversal barriers (junctions). In Figure 7, reference numerals 04k and 06f represent a barrier (for example, p-n junction). Reference numeral 15 represents a solidified globule consisting of crystallites of silicon and solvent. Reference numeral 09 represents a conductive part of substrate. In Figure 7, reference characters a, b, c (i.e., not associated with any reference numeral) represent areas of



various types of conductive whiskers. By processing the whisker with a chemical etch of silicon, the whisker is transformed into a tip with simultaneous removal of the globule (15).

[0062] EXAMPLE 3. A most typical version for realization of the matrix system of the controlled electron sources that uses the vertical arrangement of the control components is the following.

[0063] Rows of sharpened whisker-grown field emitters 01 are formed on a conducting substrate 09' of silicon having the crystallographic orientation (111) as shown in Fig. 6a. A system of parallel rows of control electrodes 08 is formed on the surface of the field emitters 01, the insulating layers 03 being placed between the field emitters 01 and the control electrodes 08. Then, an insulating glass layer 03' is deposited on the structure. After that, a set of parallel electrodes 02a and 02b are deposited onto the glass layer 03', and centrosymmetrical cavities 07 are formed at the places corresponding to the emitters so that the upper ("top") of each of the emitters 01 are in the centers of the cavities 07 being risen above their bottoms. It is important that the set of the electrodes 02a and 02b is perpendicular to the system of parallel rows of the control electrode 08. In order to obtain an emission from a given field emitter, it is necessary to apply a voltage  $V_{open}$  to a row in the system of the control electrodes 08 and, simultaneously, to apply a voltage  $V_{ext}$ , to the set of electrodes 02a and 02b. At the cross of the row and of the electrodes 02a and 02b, the sum voltage  $V_{open} + V_{ext}$ , initiates the emission.

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